

ABSTRACT OF THE DISCLOSURE

The resist composition of the invention comprises at least one resist compound and at least one acid or base generator capable of directly or indirectly generating an acid or a base by exposure to radiation. The resist compound satisfies all the following requirements: a) containing at least one acid-dissociating functional group in molecule thereof, b) containing at least one kind of functional group selected from the group consisting of urea group, urethane group, amido group and imido group in a molecule thereof, c) having a molecular weight of 500 to 5,000, d) having a branched structure, and e) satisfying the formula: $3 \leq F \leq 5$, wherein F is represented by (number of total atoms)/(number of total carbon atoms - number of total oxygen atoms). The resist composition has a high sensitivity, a high resolution, a high heat resistance and a good solubility to solvents.